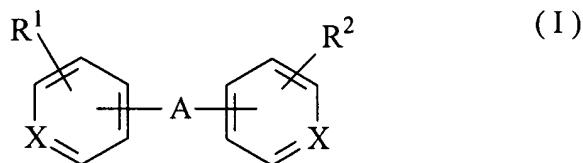


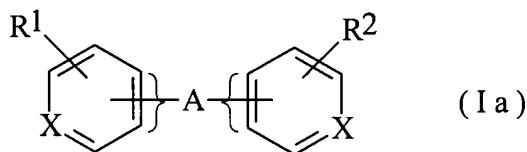
**AMENDMENTS TO THE CLAIMS**

1. (Currently amended) A negative type resist composition comprising ~~alkali-soluble resin, polyvinyl phenol-based resin in which the phenolic hydroxyl group is partially alkyl-etherified, acid generator, crosslinking agent, and a basic compound represented by the following formula (I)~~



wherein, A represents sulfide group, disulfide group or bivalent aliphatic hydrocarbon residue which may be optionally interrupted by imino group, [sulfide group, or disulfide group.] X represents nitrogen atom or C(NH<sub>2</sub>), and R<sup>1</sup> and R<sup>2</sup> independently represent hydrogen or alkyl provided that, when X represents C(NH<sub>2</sub>), A represents sulfide group or disulfide group.

2. (Original) The negative type resist composition according to claim 1, wherein the basic compound of the formula (I) is represented by the following formula (Ia):



wherein, A, X, R<sup>1</sup> and R<sup>2</sup> are the same as defined in claim 1, and the marks, "}" and "{", indicate that A is positioned on 3-position, or 4-position on the six-membered rings with respect to X.

3. (Canceled)

4. (Canceled)

5. (Currently amended) The negative type resist composition according to ~~claim 4~~ claim 1, wherein the basic compound of formula ~~(Ib)-~~(I) is selected from 1,2-di(4-pyridyl)ethane, 1,3-di(4-pyridyl)propane, 1,2-di(4-pyridyl)ethylene and bis(3-pyridylmethyl)amine.

6. (Canceled)

7. (Currently amended) The negative type resist composition according to ~~claim 6~~ claim 1, wherein the basic compound of formula ~~(Ib)-~~(I) is selected from 4,4'-dipyridylsulfide and 4,4'-dipyridyldisulfide.

8. (Canceled)

9. (Previously presented) The negative type resist composition according to claim 1, wherein the acid generator is a sulfonic ester of N-hydroxyimide compound.

10. (Original) The negative type resist composition according to claim 1, wherein composition ratio of the basic compound of formula (I) is between 0.02 and 1 wt %, based on the total solid content in the composition.

11. (Original) The negative type resist composition according to claim 1, wherein A is a linear alkylene having 2 to 4 carbon atoms, linear alkenylene having 2 to 4 carbon atoms or iminobisalkylene having 2 to 6 carbon atoms.

12. (Original) The negative type resist composition according to claim 1, wherein A is a sulfide group or a disulfide group.

13. (Original) The negative type resist composition according to claim 1, wherein A is selected from the group consisting of methylene, ethylene, vinylene, trimethylene, tetramethylene, iminobismethylene, sulfide and disulfide.